

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	177	(216/23).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/02/09 15:34
L2	268	(216/80).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/02/09 15:36
L3	775	(216/97).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/02/09 15:36
L4	1204	(216/79).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/02/09 15:36
L5	202	(349/192).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/02/09 15:41
L6	934	(349/187).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/02/09 15:43
L7	264	((349/158).CCLS.) and etch\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2006/02/09 15:38
L8	1524	((349/158).CCLS.)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2006/02/09 15:38
L9	21	(ashing (dry plasma) adj2 etch\$3) with (wash\$3 clean\$3) same glass adj2 substrate same (impurity impurities contamination contaminants)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2006/02/09 15:38
L10	0	((ashing (dry plasma) adj2 etch\$3) with (wash\$3 clean\$3) same glass adj2 substrate same (impurity impurities contamination contaminants)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2006/02/09 15:38
L11	415	(LCD liquid adj crystal) and (ashing (dry plasma) adj2 etch\$3) with (wash\$3 clean\$3) same substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2006/02/09 15:38
L12	5	((LCD liquid adj crystal) and (ashing (dry plasma) adj2 etch\$3) with (wash\$3 clean\$3) same substrate).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2006/02/09 15:39
L13	894	(438/459).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/02/09 15:40
L14	896	(438/30).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/02/09 15:40